



PATENT  
Attorney Docket No. 4329.3139

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: )  
)  
MITSUAKI IZUHA ET AL. )  
)  
Application No.: 10/660,555 ) Group Art Unit: Unknown  
)  
Filed: September 12, 2003 ) Examiner: Unknown  
)  
For: MOSFET FORMED BY USING )  
SALICIDE PROCESS AND )  
METHOD OF MANUFACTURING )  
THE SAME )

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

**INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. § 1.97(b)**

Pursuant to 37 C.F.R. §§ 1.56 and 1.97(b), applicants bring to the attention of the Examiner the documents listed on the attached PTO 1449. This Information Disclosure Statement is being filed within three months of the filing date of the above-referenced application.

Copies of the listed documents are attached.

Applicants respectfully request that the Examiner consider the listed documents and indicate that they were considered by making appropriate notations on the attached form.

The following document listed on the attached PTO 1449 is not in English:

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Japanese Laid-Open Patent Application No. 11-214680. The relevance of this document is discussed on page 2 of the present application. An English-language abstract of the document is also provided.

In lieu of a statement of relevance or translation of the non-English document, an English language abstract is provided.

This submission does not represent that a search has been made or that no better art exists and does not constitute an admission that each or all of the listed documents are material or constitute "prior art." If the Examiner applies any of the documents as prior art against any claim in the application and applicants determine that the cited documents do not constitute "prior art" under United States law, applicants reserve the right to present to the office the relevant facts and law regarding the appropriate status of such documents.

Applicants further reserve the right to take appropriate action to establish the patentability of the disclosed invention over the listed documents, should one or more of the documents be applied against the claims of the present application.

If there is any fee due in connection with the filing of this Statement, please charge the fee to our Deposit Account No. 06-0916.

Respectfully submitted,

FINNEGAN, HENDERSON, FARABOW,  
GARRETT & DUNNER, L.L.P.

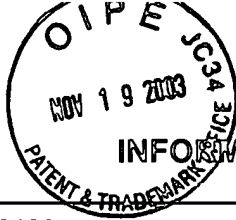
Dated: 11/19/03

By: 

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OMB No. 0651-0011

## INFORMATION DISCLOSURE CITATION

|                  |                    |            |            |
|------------------|--------------------|------------|------------|
| Atty. Docket No. | 4329.3139          | Appln. No. | 10/660,555 |
| Applicant        | Izuha et al.       |            |            |
| Filing Date      | September 12, 2003 | Group:     | Unknown    |

## U.S. PATENT DOCUMENTS

| Examiner Initial* | Document Number | Issue Date | Name | Class | Sub Class | Filing Date If Appropriate |
|-------------------|-----------------|------------|------|-------|-----------|----------------------------|
|                   |                 |            |      |       |           |                            |
|                   |                 |            |      |       |           |                            |
|                   |                 |            |      |       |           |                            |
|                   |                 |            |      |       |           |                            |
|                   |                 |            |      |       |           |                            |

## FOREIGN PATENT DOCUMENTS

| Document Number | Publication Date | Country | Class | Sub Class | Translation Yes or No |
|-----------------|------------------|---------|-------|-----------|-----------------------|
| 11-214680       | 8/6/99           | Japan   |       |           | Abstract              |
|                 |                  |         |       |           |                       |
|                 |                  |         |       |           |                       |
|                 |                  |         |       |           |                       |
|                 |                  |         |       |           |                       |

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

|  |   |
|--|---|
|  | Maa et al., "Stability Improvement of Nickel Silicide with Co Interlayer on Si, Polysilicon and SiGe," Mat. Res. Soc. Symp. Proc. (2001), 670:K6.9.1-K6.9.6 |
|  | Wang et al., "Silicide formation and stability of Ti/SiGe and Co/SiGe," Thin Solid Films (1995), pp. 555-560  |
|  |   |
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|---|---|
| Examiner  | Date Considered   |
| *Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. |   |
| Form PTO 1449   | Patent and Trademark Office - U.S. Department of Commerce |